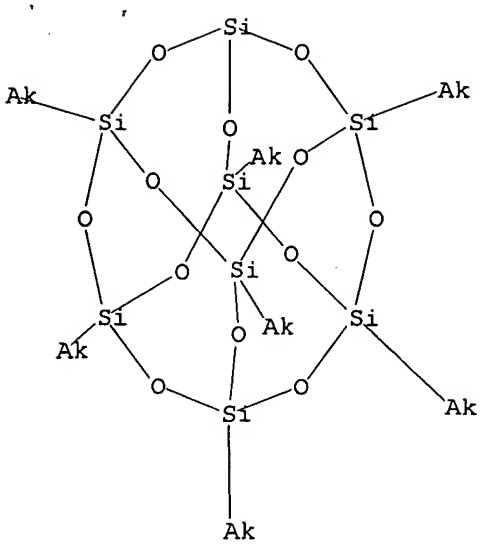
```
FILE 'HOME' ENTERED AT 11:45:17 ON 18 MAY 2005

=> file reg
COST IN U.S. DOLLARS                                    SINCE FILE      TOTAL
                                                           ENTRY    SESSION
FULL ESTIMATED COST                                         0.21       0.21

FILE 'REGISTRY' ENTERED AT 11:45:31 ON 18 MAY 2005
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
COPYRIGHT (C) 2005 American Chemical Society (ACS)

Property values tagged with IC are from the ZIC/VINITI data file
provided by InfoChem.

STRUCTURE FILE UPDATES:   17 MAY 2005  HIGHEST RN 850605-77-5
DICTIONARY FILE UPDATES:  17 MAY 2005  HIGHEST RN 850605-77-5

New CAS Information Use Policies, enter HELP USAGETERMS for details.

TSCA INFORMATION NOW CURRENT THROUGH JANUARY 18, 2005

  Please note that search-term pricing does apply when
  conducting SmartSELECT searches.

**********************************************************************
*                                                                    *
* The CA roles and document type information have been removed from *
* the IDE default display format and the ED field has been added,   *
* effective March 20, 2005.  A new display format, IDERL, is now    *
* available and contains the CA role and document type information. *
*                                                                    *
**********************************************************************

Crossover limits have been increased.  See HELP CROSSOVER for details.

Experimental and calculated property data are now available. For more
information enter HELP PROP at an arrow prompt in the file or refer
to the file summary sheet on the web at:
http://www.cas.org/ONLINE/DBSS/registryss.html

=> ....Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end


=>
Uploading C:\Program Files\Stnexp\Queries\10792306.str

L1      STRUCTURE UPLOADED

=> que L1

L2   QUE L1

=> d
L2 HAS NO ANSWERS
L1              STR
```




O

Structure attributes must be viewed using STN Express query preparation.
L2 QUE ABB=ON PLU=ON L1

=> s l2 sss sam
SAMPLE SEARCH INITIATED 11:46:23 FILE 'REGISTRY'
SAMPLE SCREEN SEARCH COMPLETED - 224 TO ITERATE

100.0% PROCESSED 224 ITERATIONS 17 ANSWERS
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
BATCH **COMPLETE**
PROJECTED ITERATIONS: 3583 TO 5377
PROJECTED ANSWERS: 93 TO 587

L3 17 SEA SSS SAM L1

=> ....Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=> screen 2067

L4 SCREEN CREATED

=>
Uploading C:\Program Files\Stnexp\Queries\10792306-1.str

L5 STRUCTURE UPLOADED

=> que L5 AND L4

L6 QUE L5 AND L4

=> d

```
L6 HAS NO ANSWERS
L4              SCR 2067
L5              STR

* STRUCTURE DIAGRAM TOO LARGE FOR DISPLAY -  AVAILABLE VIA OFFLINE PRINT *

Structure attributes must be viewed using STN Express query preparation.
L6              QUE  ABB=ON  PLU=ON  L5 AND L4


=> s l6 sss sam
SAMPLE SEARCH INITIATED 11:47:43 FILE 'REGISTRY'
SAMPLE SCREEN SEARCH COMPLETED -     15 TO ITERATE

100.0% PROCESSED      15 ITERATIONS                                2 ANSWERS
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS:  ONLINE  **COMPLETE**
                        BATCH   **COMPLETE**
PROJECTED ITERATIONS:           68 TO      532
PROJECTED ANSWERS:               2 TO      124

L7            2 SEA SSS SAM L5 AND L4

=> ....Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end


=> screen 2067

L8    SCREEN CREATED

=>
Uploading C:\Program Files\Stnexp\Queries\10792306-2.str

L9      STRUCTURE UPLOADED

=> que L9 AND L8

L10  QUE L9 AND L8

=> s l10 sss sam
SAMPLE SEARCH INITIATED 11:48:06 FILE 'REGISTRY'
SAMPLE SCREEN SEARCH COMPLETED -     23 TO ITERATE

100.0% PROCESSED      23 ITERATIONS                                0 ANSWERS
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS:  ONLINE  **COMPLETE**
                        BATCH   **COMPLETE**
PROJECTED ITERATIONS:          173 TO      747
PROJECTED ANSWERS:               0 TO        0

L11           0 SEA SSS SAM L9 AND L8

=> d his

     (FILE 'HOME' ENTERED AT 11:45:17 ON 18 MAY 2005)

     FILE 'REGISTRY' ENTERED AT 11:45:31 ON 18 MAY 2005
L1              STRUCTURE UPLOADED
L2              QUE L1
L3           17 S  L2 SSS SAM
L4              SCREEN 2067
L5              STRUCTURE UPLOADED
L6              QUE L5 AND L4
L7            2 S L6 SSS SAM
```

```
L8              SCREEN 2067
L9              STRUCTURE UPLOADED
L10             QUE L9 AND L8
L11           0 S L10 SSS SAM

=> ....Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end


=> screen 2067

L12   SCREEN CREATED

=>
Uploading C:\Program Files\Stnexp\Queries\10792306-3.str

L13     STRUCTURE UPLOADED

=> que L13 AND L12

L14  QUE L13 AND L12

=> s l14 sss sam
SAMPLE SEARCH INITIATED 11:48:53 FILE 'REGISTRY'
SAMPLE SCREEN SEARCH COMPLETED -     18 TO ITERATE

100.0% PROCESSED      18 ITERATIONS                                0 ANSWERS
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS:  ONLINE  **COMPLETE**
                        BATCH   **COMPLETE**
PROJECTED ITERATIONS:          106 TO      614
PROJECTED ANSWERS:               0 TO        0

L15           0 SEA SSS SAM L13 AND L12

=> d his

     (FILE 'HOME' ENTERED AT 11:45:17 ON 18 MAY 2005)

     FILE 'REGISTRY' ENTERED AT 11:45:31 ON 18 MAY 2005
L1              STRUCTURE UPLOADED
L2              QUE L1
L3           17 S  L2 SSS SAM
L4              SCREEN 2067
L5              STRUCTURE UPLOADED
L6              QUE L5 AND L4
L7            2 S L6 SSS SAM
L8              SCREEN 2067
L9              STRUCTURE UPLOADED
L10             QUE L9 AND L8
L11           0 S L10 SSS SAM
L12             SCREEN 2067
L13             STRUCTURE UPLOADED
L14             QUE L13 AND L12
L15           0 S L14 SSS SAM

=> s l3 or l7 or l11 or l15
L16         17 L3 OR L7 OR L11 OR L15

=> FIL HCAPLUS, CAPLUS, USPATFULL
COST IN U.S. DOLLARS                          SINCE FILE      TOTAL
                                                 ENTRY    SESSION
FULL ESTIMATED COST                               2.58       2.79

FILE 'HCAPLUS' ENTERED AT 11:49:13 ON 18 MAY 2005
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
```

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COPYRIGHT (C) 2005 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'CAPLUS' ENTERED AT 11:49:13 ON 18 MAY 2005
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
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FILE 'USPATFULL' ENTERED AT 11:49:13 ON 18 MAY 2005
CA INDEXING COPYRIGHT (C) 2005 AMERICAN CHEMICAL SOCIETY (ACS)

=> s l16
L17 33 L16

=> s (resist or photoresist)
L18 461977 (RESIST OR PHOTORESIST)

=> s l17 and l18
L19 2 L17 AND L18

=> duplicates remove l19
DUPLICATE PREFERENCE IS 'HCAPLUS, CAPLUS'
KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n
PROCESSING COMPLETED FOR L19
L20 1 DUPLICATE REMOVE L19 (1 DUPLICATE REMOVED)

=> d l20 ibib hitstr

L20 ANSWER 1 OF 1 HCAPLUS COPYRIGHT 2005 ACS on STN DUPLICATE 1
ACCESSION NUMBER: 2004:779219 HCAPLUS
DOCUMENT NUMBER: 141:285810
TITLE: Positive-working **resist** composition containing acrylic resin with polyhedral oligomeric silsesquioxane group
INVENTOR(S): Adegawa, Yutaka
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 55 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|---|---|---|---|---|
| JP 2004264479 | A2 | 20040924 | JP 2003-53704 | 20030228 |

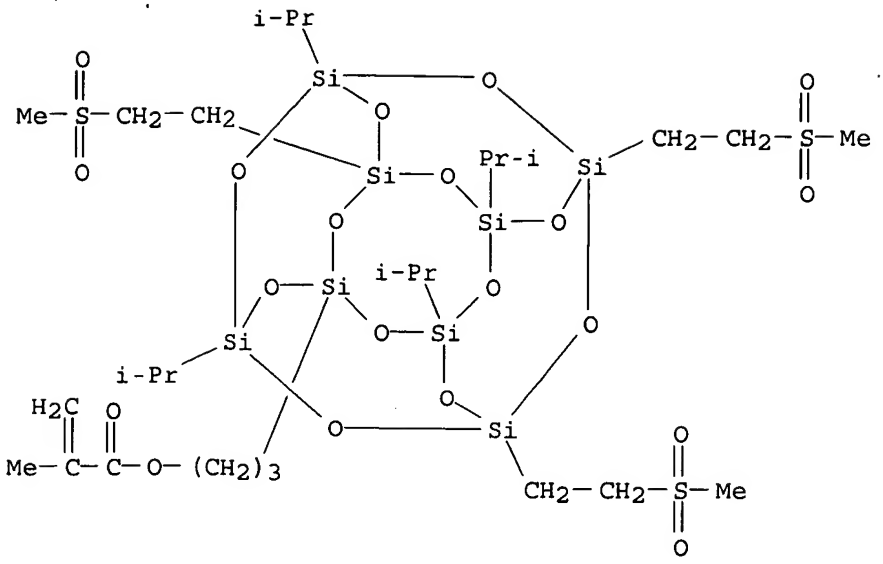
PRIORITY APPLN. INFO.: JP 2003-53704 20030228

IT **760971-81-1P**
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(pos.-working **resist** composition containing acrylic resin with polyhedral oligomeric silsesquioxane group)

RN 760971-81-1 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 3-[3,5,11,13-tetrakis(1-methylethyl)-7,9,15-tris[2-(3-methylsulfonyl)ethyl]pentacyclo[9.5.1.13,9.15,15.17,13]octasiloxan-1-yl]propyl ester, polymer with 1,1-dimethylethyl 2-propenoate (9CI) (CA INDEX NAME)

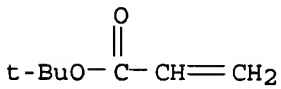
CM 1

CRN 760970-40-9
CMF C28 H60 O20 S3 Si8



CM 2

CRN 1663-39-4
CMF C7 H12 O2



=> d his

(FILE 'HOME' ENTERED AT 11:45:17 ON 18 MAY 2005)

FILE 'REGISTRY' ENTERED AT 11:45:31 ON 18 MAY 2005
L1 STRUCTURE UPLOADED
L2 QUE L1
L3 17 S L2 SSS SAM
L4 SCREEN 2067
L5 STRUCTURE UPLOADED
L6 QUE L5 AND L4
L7 2 S L6 SSS SAM
L8 SCREEN 2067
L9 STRUCTURE UPLOADED
L10 QUE L9 AND L8
L11 0 S L10 SSS SAM
L12 SCREEN 2067
L13 STRUCTURE UPLOADED
L14 QUE L13 AND L12
L15 0 S L14 SSS SAM
L16 17 S L3 OR L7 OR L11 OR L15

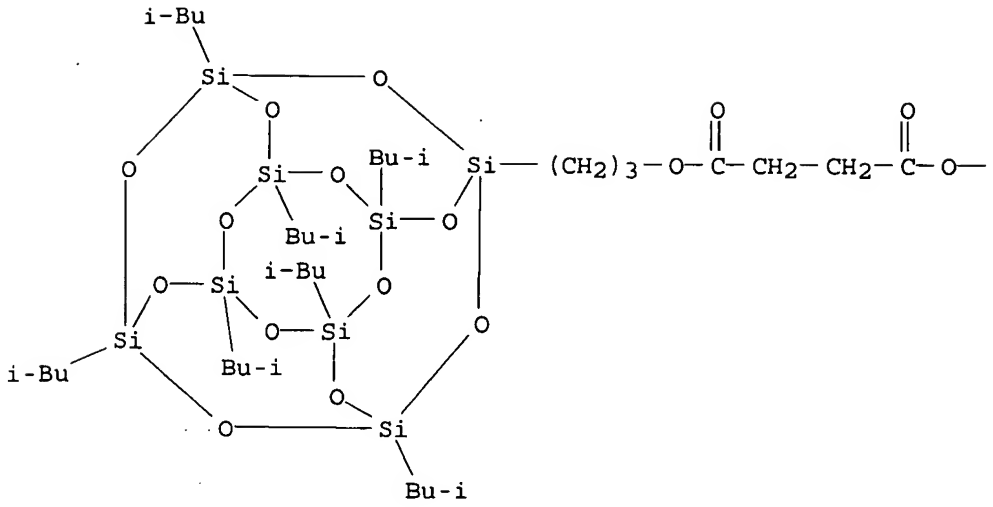
FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 11:49:13 ON 18 MAY 2005
L17 33 S L16
L18 461977 S (RESIST OR PHOTORESIST)
L19 2 S L17 AND L18
L20 1 DUPLICATE REMOVE L19 (1 DUPLICATE REMOVED)

=> s l17 and composition
L21 7 L17 AND COMPOSITION

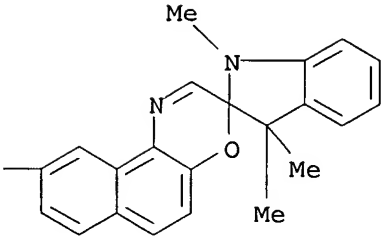
=> s l21 not l20
L22 6 L21 NOT L20

```
=> duplicates remove l22
DUPLICATE PREFERENCE IS 'HCAPLUS, CAPLUS, USPATFULL'
KEEP DUPLICATES FROM MORE THAN ONE FILE?  Y/(N):n
PROCESSING COMPLETED FOR L22
L23            4 DUPLICATE REMOVE L22 (2 DUPLICATES REMOVED)

=> d l23 1-4 ibib hitstr

L23  ANSWER 1 OF 4  HCAPLUS  COPYRIGHT 2005 ACS on STN DUPLICATE 1
ACCESSION NUMBER:         2004:413032  HCAPLUS
DOCUMENT NUMBER:          140:431465
TITLE:                    Photochromic compositions and light
                          transmissible articles
INVENTOR(S):              Evans, Richard Alexander; Skidmore, Melissa Ann; Yee,
                          Lachlan Hartley; Hanley, Tracey Lee; Lewis, David
                          Andrew
PATENT ASSIGNEE(S):       Polymers Australia Pty. Limited, Australia
SOURCE:                   PCT Int. Appl., 118 pp.
                          CODEN: PIXXD2
DOCUMENT TYPE:            Patent
LANGUAGE:                 English
FAMILY ACC. NUM. COUNT:   1
PATENT INFORMATION:

     PATENT NO.           KIND   DATE        APPLICATION NO.         DATE
     ---------------      ----   --------    --------------------    --------
     WO 2004041961         A1    20040521    WO 2003-AU1453          20031103
         W:  AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH,
             CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD,
             GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC,
             LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NI, NO,
             NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ,
             TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW
         RW: BW, GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ,
             BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE,
             ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK,
             TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG
PRIORITY APPLN. INFO.:                   AU 2002-952454      A  20021104
                                         AU 2003-903133      A  20030620

IT   692726-67-3P
     RL: IMF (Industrial manufacture); TEM (Technical or engineered material
     use); PREP (Preparation); USES (Uses)
        (photochromic compns. based on photochromic moieties with
        pendent oligomers and their preparation and articles comprising them)
RN   692726-67-3  HCAPLUS
CN   Butanedioic acid, 1,3-dihydro-1,3,3-trimethylspiro[2H-indole-2,3'-
     [3H]naphth[2,1-b][1,4]oxazin]-9'-yl 3-[heptakis(2-
     methylpropyl)pentacyclo[9.5.1.13,9.15,15.17,13]octasiloxanyl]propyl ester
     (9CI)  (CA INDEX NAME)
```

PAGE 1-A



PAGE 1-B



REFERENCE COUNT: 4 THERE ARE 4 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L23 ANSWER 2 OF 4 HCAPLUS COPYRIGHT 2005 ACS on STN DUPLICATE 2
ACCESSION NUMBER: 2004:20131 HCAPLUS
DOCUMENT NUMBER: 140:102097
TITLE: Reliable sealing of liquid crystal panels and photocurable sealants with good substrate adhesion therefor
INVENTOR(S): Yamamoto, Hitoshi; Sasata, Yasuyuki; Harufuji, Tatsuji; Hirano, Yukio
PATENT ASSIGNEE(S): Chisso Corp., Japan; Chisso Petrochemical Corporation
SOURCE: Jpn. Kokai Tokkyo Koho, 23 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|---|---|---|---|---|
| JP 2004004612 | A2 | 20040108 | JP 2003-70642 | 20030314 |
| PRIORITY APPLN. INFO.: | | | JP 2002-92333 A | 20020328 |

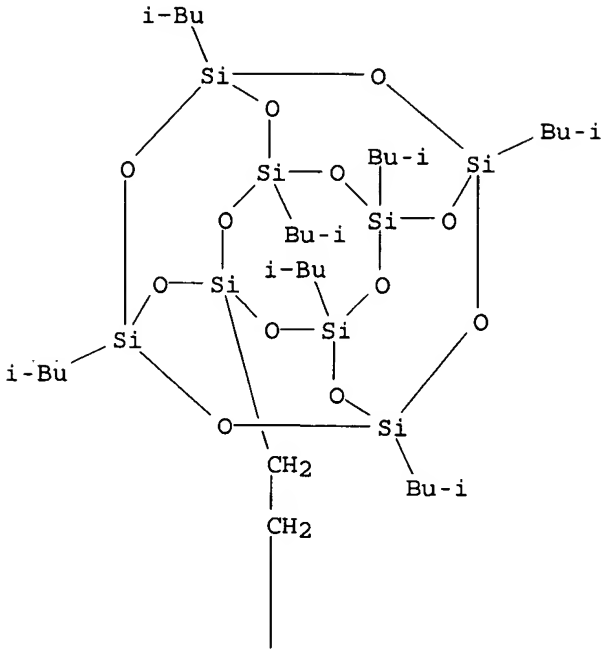
IT **643018-12-6P**
RL: DEV (Device component use); IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(low-moisture-permeable and long-life photocurable sealants containing POSS derivs. for LCD sealing)
RN 643018-12-6 HCAPLUS
CN 2-Propenoic acid, 4-[2-[heptakis(2-methylpropyl)pentacyclo[9.5.1.13,9.15,15.17,13]octasiloxanyl]ethyl]-1,2-cyclohexanediyl ester, polymer with 2,2'-[(1-methylethylidene)bis(4,1-phenyleneoxymethylene)]bis[oxirane]

homopolymer 2-methyl-2-propenoate (9CI)  (CA INDEX NAME)

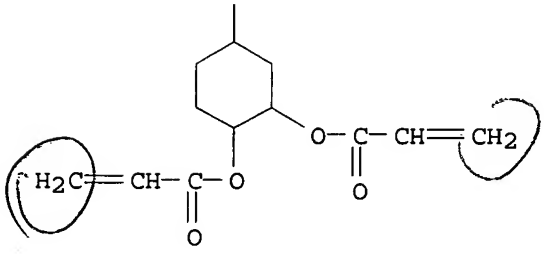
CM  1

CRN  643018-03-5
CMF  C42 H82 O16 Si8

PAGE 1-A




PAGE 2-A

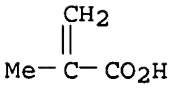



CM  2

CRN  39290-46-5
CMF  (C21 H24 O4)x . x C4 H6 O2

CM  3

CRN  79-41-4
CMF  C4 H6 O2

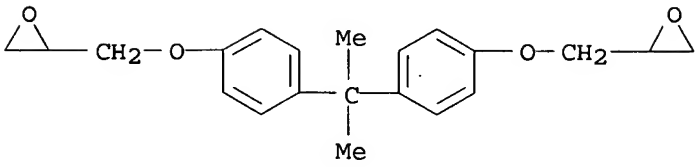



CM  4

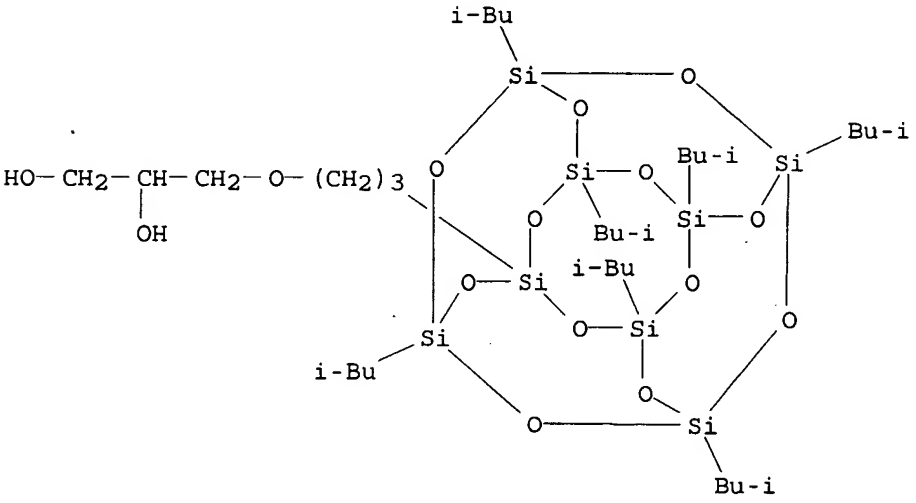
CRN 25085-99-8
CMF (C21 H24 O4)x
CCI PMS

CM 5

CRN 1675-54-3
CMF C21 H24 O4



IT **480439-49-4**
RL: RCT (Reactant); RACT (Reactant or reagent)
(low-moisture-permeable and long-life photocurable sealants containing POSS derivs. for LCD sealing)
RN 480439-49-4 HCAPLUS
CN 1,2-Propanediol, 3-[3-[heptakis(2-methylpropyl)pentacyclo[9.5.1.13,9.15,15.17,13]octasiloxanyl]propoxy]- (9CI) (CA INDEX NAME)



L23 ANSWER 3 OF 4 CAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2004:779219 CAPLUS
DOCUMENT NUMBER: 141:285810
TITLE: Positive-working resist **composition** containing acrylic resin with polyhedral oligomeric silsesquioxane group
INVENTOR(S): Adegawa, Yutaka
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 55 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|---|---|---|---|---|
| JP 2004264479 | A2 | 20040924 | JP 2003-53704 | 20030228 |
| PRIORITY APPLN. INFO.: | | | JP 2003-53704 | 20030228 |

IT **760971-81-1P**

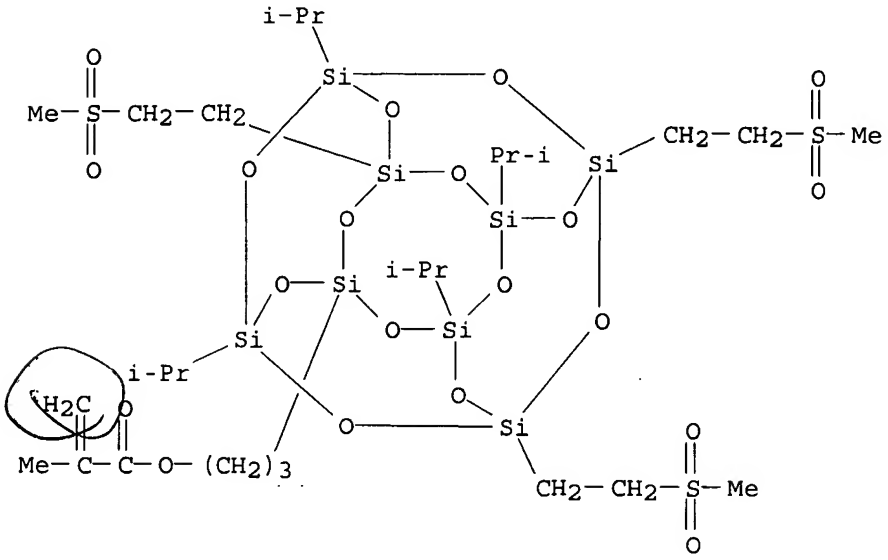
RL:· IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(pos.-working resist **compn**. containing acrylic resin with polyhedral oligomeric silsesquioxane group)

RN 760971-81-1 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-[3,5,11,13-tetrakis(1-methylethyl)-7,9,15-tris[2-(3-methylsulfonyl)ethyl]pentacyclo[9.5.1.13,9.15,15.17,13]octasiloxan-1-yl]propyl ester, polymer with 1,1-dimethylethyl 2-propenoate (9CI) (CA INDEX NAME)

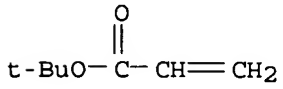
CM 1

CRN 760970-40-9
CMF C28 H60 O20 S3 Si8



CM 2

CRN 1663-39-4
CMF C7 H12 O2



L23 ANSWER 4 OF 4 USPATFULL on STN

| | |
|---|---|
| ACCESSION NUMBER: | 2004:39520 USPATFULL |
| TITLE: | Castable shape memory polymers |
| INVENTOR(S): | Mather, Patrick T., Storrs, CT, UNITED STATES<br>Liu, Changdeng, Storrs, CT, UNITED STATES |

| | NUMBER | KIND | DATE |
|---|---|---|---|
| PATENT INFORMATION: | US 2004030062 | A1 | 20040212 |
| APPLICATION INFO.: | US 2003-425451 | A1 | 20030429 (10) |

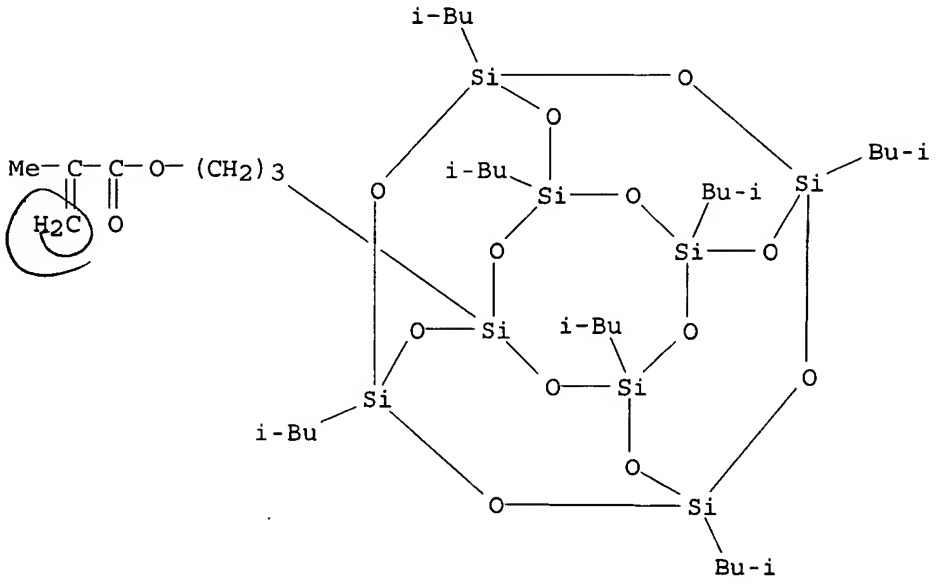
| | NUMBER | DATE |
|---|---|---|
| PRIORITY INFORMATION: | US 2002-377544P | 20020502 (60) |

| | |
|---|---|
| DOCUMENT TYPE: | Utility |
| FILE SEGMENT: | APPLICATION |
| LEGAL REPRESENTATIVE: | CUMMINGS & LOCKWOOD, Granite Square, 700 State Street, P.O. Box 1960, New Haven, CT, 06509-1960 |

NUMBER OF CLAIMS: 35
EXEMPLARY CLAIM: 1
NUMBER OF DRAWINGS: 3 Drawing Page(s)
LINE COUNT: 775
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
IT **620179-62-6P**
(castable shape memory polymers)
RN 620179-62-6 USPATFULL
CN 2-Propenoic acid, 2-methyl-, oxybis(2,1-ethanediyloxy-2,1-ethanediyl) ester, polymer with butyl 2-methyl-2-propenoate, 3-[heptakis(2-methylpropyl)pentacyclo[9.5.1.13,9.15,15.17,13]octasiloxanyl]propyl 2-methyl-2-propenoate and methyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

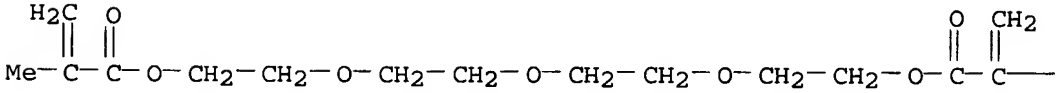
CRN 307531-94-8
CMF C35 H74 O14 Si8




CM 2

CRN 109-17-1
CMF C16 H26 O7

PAGE 1-A



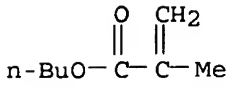

PAGE 1-B

—Me

CM 3

CRN 97-88-1

CMF C8 H14 O2



CM 4

CRN 80-62-6
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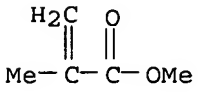


L26 ANSWER 2 OF 2 HCAPLUS COPYRIGHT 2005 ACS on STN DUPLICATE 2
ACCESSION NUMBER: 2004:779218 HCAPLUS
DOCUMENT NUMBER: 141:285809
TITLE: Positive-working resist composition containing acrylic resin with lactone and polyhedral oligomeric silsesquioxane groups
INVENTOR(S): Adegawa, Yutaka
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 62 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|---|---|---|---|---|
| JP 2004264478 | A2 | 20040924 | JP 2003-53703 | 20030228 |

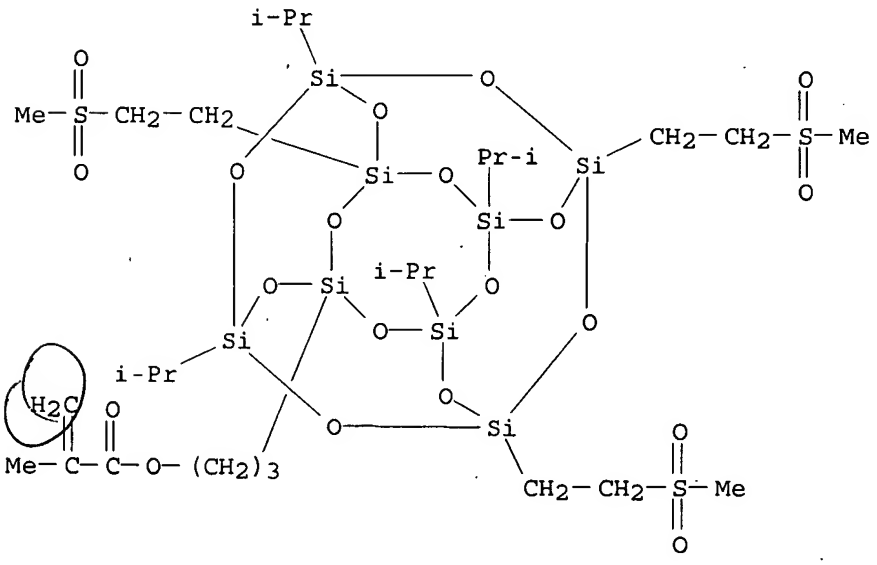
PRIORITY APPLN. INFO.: JP 2003-53703 20030228

IT **760970-41-0P 760970-48-7P**
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(pos. resist composition containing alkali-soluble acrylic resin with lactone and POSS groups)

RN 760970-41-0 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 1,1-dimethylethyl ester, polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate and 3-[3,5,11,13-tetrakis(1-methylethyl)-7,9,15-tris[2-(methylsulfonyl)ethyl]pentacyclo[9.5.1.13,9.15,15.17,13]octasiloxanyl]propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

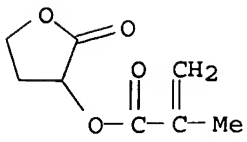
CM 1

CRN 760970-40-9
CMF C28 H60 O20 S3 Si8



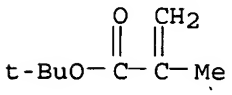

CM 2

CRN 195000-66-9
CMF C8 H10 O4



CM 3

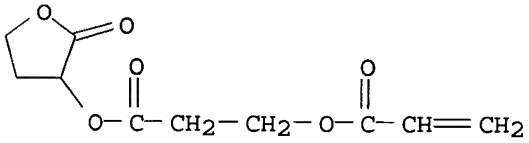
CRN 585-07-9
CMF C8 H14 O2



RN 760970-48-7 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 3-[3,5,11,13-tetrakis(1-methylethyl)-7,9,15-tris[2-(methylsulfonyl)ethyl]pentacyclo[9.5.1.13,9.15,15.17,13]octasiloxanyl]propyl ester, polymer with 1,1-dimethylethyl 2-propenoate, 3-oxo-3-[(tetrahydro-2-oxo-3-furanyl)oxy]propyl 2-propenoate and 3-[3,7,13-tris[3-(methoxysulfonyl)propyl]-5,9,11,15-tetrakis(1-methylethyl)pentacyclo[9.5.1.13,9.15,15.17,13]octasiloxan-1-yl]propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

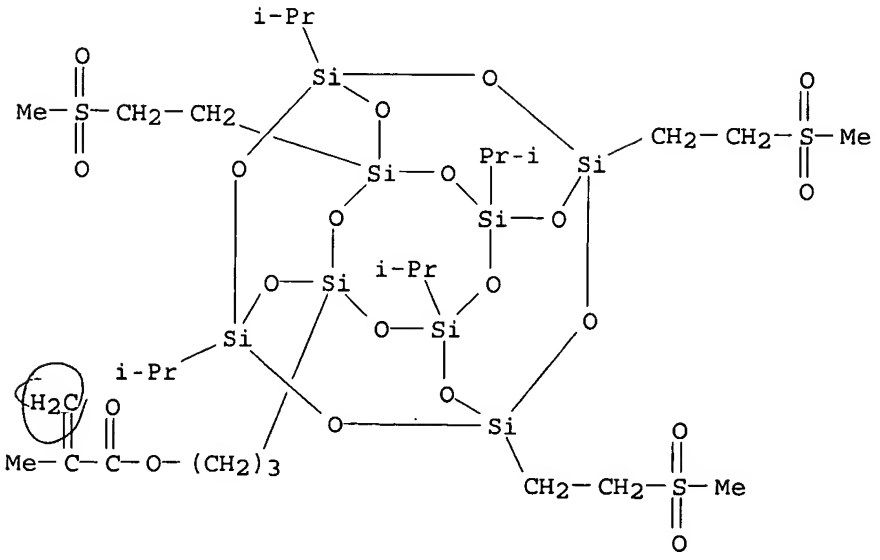
CM 1

CRN 760970-45-4
CMF C10 H12 O6



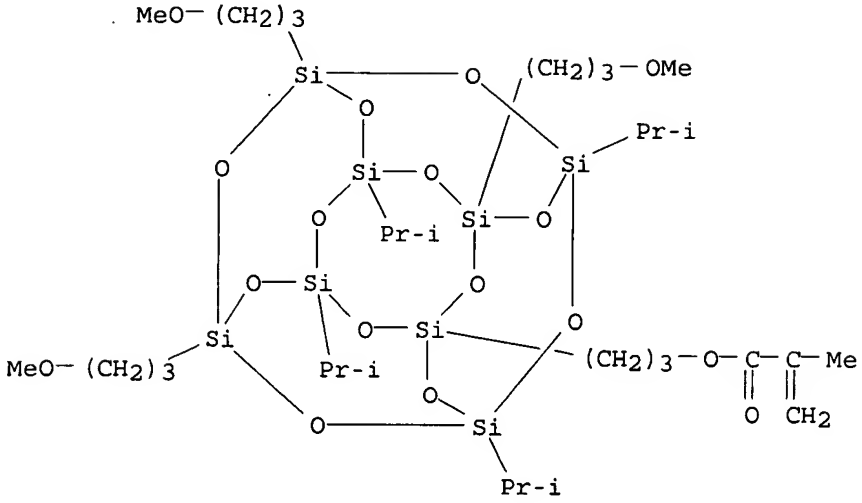
CM 2

CRN 760970-40-9
CMF C28 H60 O20 S3 Si8



CM 3

CRN 760970-38-5
CMF C31 H66 O17 Si8



CM 4

CRN 1663-39-4
CMF C7 H12 O2